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Patent

TUSSN 09/375,267

Atty Docket 99108

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of: )  
HANS LOSCHNER, ET AL. ) Group Art Unit:  
For: PARTICLE MULTIBEAM LITHOGRAPHY ) 2881  
Serial No. 09/375,267 09/375 627 HN ) Examiner:  
Filed: August 17, 1999 ) Anthony Quash  
 ) EXPEDITED PROCEDURE

11/D(E)  
FJONES  
2-27-02

**AMENDMENT C UNDER RULE 116 AFTER FINAL REJECTION**

TO:  
Assistant Commissioner of Patents  
Washington, D.C. 20231

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Dear Sir:

In response to the Examiner's Action, made final, mailed August 14, 2001, applicant requests that the subject patent application be amended as follows:

**IN THE CLAIMS:**

Please amend claim 1 in the manner set forth below. A clean copy of claim 1 is enclosed herewith.

1. (Twice amended) An apparatus for multibeam lithography by means of electrically charged particles, comprising an illumination system having a particle source, the illumination system producing an illuminating beam of said electrically charged particles, and a multibeam optical system positioned after the illumination system as seen in the direction of the beam, said multibeam optical system comprising at least one aperture plate having an array of a plurality of apertures to form a plurality of sub-beams, wherein the multibeam optical system focuses the sub-beams onto the surface of a substrate for simultaneously writing a plurality of different

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service on first-class mail in an envelope addressed for Assistant Commissioner of Patents and Trademarks, Washington, DC 20231 on:

Date 11/9/01 2 8. W git